2024년 1월 25일(목), 15:30-17:15
Room I(203),2층

D. Thin Film Process Technology 분과

[TI3-D] Ferroelectrics

좌장: 최병준 교수(서울과학기술대학교), 김건환 교수(연세대학교)

TI3-D-1 15:30-15:45	Mitigation of Field-driven Dynamic Phase Evolution in Ferroelectric $Hf_{0.5}Zr_{0.5}O_2$ Films by Adopting Oxygen-supplying Electrode Younghwan Lee[1], Se Hyun Kim[2], Hyun Woo Jeong[2], Geun Hyeong Park[2], Jaewook Lee[2], Young Yong Kim[3], and Min Hyuk Park[1,2] [1]Research Institute of Advanced Materials, Seoul National University, [2]Department of Materials Science and Engineering, Seoul National University, [3]Beamline Division, Pohang Accelerator Laboratory
TI3-D-2 15:45-16:00	Interface Engineering for Enhancement of Ferroelectricity in Sub-5 nm Ultrathin $Hf_{0.5}Zr_{0.5}O_2$ Films Se Hyun Kim[1], Younghwan Lee[2], Dong Hyun Lee[1], and Min Hyuk Park[1,2] [1]Department of Mcrystaterials Science and Engineering, Seoul National University, [2]Research Institute of Advanced Materials, Seoul National University
TI3-D-3 16:00-16:15	Synergistic Impact of Al_2O_3 Capping Layer and Deposition Temperature for Enhancing the Ferroelectricity of Undoped HfO_2 Thin Films Sang Han Ko and Sung Min Yoon Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University
TI3-D-4 16:15-16:30	CF_4 Plasma Passivation on Laminated-ALD HZO MFIS-FeFET Kyungsoo Park[1], Chulwon Chung[2], Boncheol Ku[1], Seung Hyeon Yun[1], Junhyeok Park[1], Yu Jeong Choi[1], and Changhwan Choi[1] [1]Division of Materials Science and Engineering, Hanyang University, [2]Deparment of Energy Engineering, Hanyang University
TI3-D-5 16:30-16:45	Development of Lab-Scale Pulsed Laser Annealing (PLA) System for $Hf_xZr_{1-x}O_2$ Thin Film Crystallization Hyeonsik Kim[1,2], Hyojin Yang[2], Sejun Park[2], Jong-Ho Bae[2], and Inhee Cho[1] [1]Korea-Russia Innovation Center, KITECH, [2]School of Electrical Engineering, Kookmin University

TI3-D-6 16:45-17:00	Ferroelectricity of $Hf_{0.5}Zr_{0.5}O_2$ Thin Film Induced at 350 ℃ by Thermally Accelerated Nucleation during Atomic Layer Deposition Jaewook Lee[1,2], Se Hyun Kim[1,2], Younghwan Lee[3], Sang-Youn Park[4], and Min Hyuk Park[1,2,3] [1]Department of Materials Science and Engineering, Seoul National University, [2]Inter-University Semiconductor Research Center, Seoul National University, [3]Research Institute of Advanced Materials College of Engineering, Seoul National University, [4]Pohang Accelerator Laboratory, POSTECH
TI3-D-7 17:00-17:15	The Impact of CF_4 Plasma Treatment on the Performance of HfO_2/IGZO Thin film Transistors (TFTs) Gyu Lee Kim, Sun bum Kim, Chan seul Lee, and Changhwan Choi Division of Materials Science and Engineering, Hanyang University